Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4526	damascene near1 (pattern structure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:48
L2	11190	damascene and semiconductor and substrate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:50
L3	992	2 and mask and ((light adj source) uv duv)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:51
L4	2163	2 and mask and ((light adj source) uv duv lithography)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:50
L5	58	4 and ((anti near reflective near coating) arc barc) and ((photo near active near dielectric) pad)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:56
L6	431	4 and ((anti near reflective near coating) arc barc sion) and ((photo near active near dielectric) polymer polymeric polyimide polysilsequioxane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:51
L7	1	4 and ((anti near reflective near coating) arc barc) and (photo near active near dielectric)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:58
L8	1	4 and ((anti near reflective near coating) sion arc barc) and (photo near active near dielectric)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 09:01

L9	144	6 and photolithographic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:34
L10	144	9 and (method process)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 09:03
L11	9	("6242344").URPN.	USPAT	OR	ON	2005/05/27 10:29
L12	11	("5635423" | "5686354" | "5741626" | "5801094" | "5863835" | "5877075" | "5882996" | "5904565" | "5906910" | "5933761" | "5935762").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 10:32

| L13 | 162 | (US-20030068864-$ or US-20030077897-$ or US-20030129827-$ or US-20040023453-$ or US-20040069410-$ or US-20040156987-$ or US-20040166240-$ or US-20050009290-$ or US-20050020003-$).did. or (US-4333227-$ or US-4339767-$ or US-4378630-$ or US-4381953-$ or US-4582565-$ or US-4734384-$ or US-4868617-$ or US-4994406-$ or US-5252848-$ or US-5504033-$ or US-5510648-$ or US-5536675-$ or US-5707896-$ or US-5753548-$ or US-5753967-$ or US-5793089-$ or US-5808347-$ or US-5817568-$ or US-5841166-$ or US-5869875-$ or US-5886382-$ or US-5895253-$ or US-5900663-$ or US-5918137-$ or US-5949104-$ or US-5950093-$).did. or (US-5989776-$ or US-6001414-$ or US-6004883-$ or US-6008114-$ or US-6025264-$ or US-6034415-$ or US-6037262-$ or US-6048772-$ or US-6051468-$ or US-6054355-$ or US-6060380-$ or US-6071806-$ or US-6074954-$ or US-6091110-$ or US-6093632-$ or US-6100163-$ or US-6100184-$ or US-6137152-$ or US-6140200-$ or US-6144096-$ or US-6144099-$ or US-6153528-$ or US-6153905-$ or US-6180490-$ or US-6180507-$ or US-6180518-$ or US-6180995-$).did. or (US-6190978-$ or US-6204166-$ or US-6211063-$ or US-6211069-$ or US-6214696-$ or US-6214698-$ or US-6215152-$ or US-6218287-$ or US-6221727-$ or US-6222233-$ or US-6251763-$ or US-6259160-$ or US-6271552-$ or US-6274923-$ or US-6284657-$ or US-6287931-$ or US-6291298-$ or US-6291333-$ or US-6294423-$ or US-6297127-$ or US-6319820-$ or US-6329280-$ or US-6348407-$ or US-6348733-$ or US-6358842-$ or US-6365952-$ or US-6372635-$).did. or (US-6376366-$ or US-6380073-$ or US-6383913-$ or US-6399432-$ or US-6399449-$ or US-6413827-$ or US-6429116-$ or US-6429129-$ or US-6436824-$ or US-6440819-$ or US-6461934-$ or US-6476445-$ or US-6486061-$ or US-6495903-$ or US-6509267-$ or US-6514860-$ or US-6518126-$ or US-6521923-$ | US-PGPUB; USPAT; JPO | OR | ON | 2005/05/27 10:38 |

L14	6	"6506979"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L15	13	"5334488"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L16	3	"6521328"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L17	9	"6349456"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L18	26	14 15 16 17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:30
L19	25	18 not 9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:30
L20	53	9 and (polyimide (fluorinated adj polyimide) polysilsequioxane benzocyclobutene (parlene adj (n f)) (amorphous adj polytetrafluorothylene))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:52
L21	2959	2 and mask and ((light adj source) uv duv photolithographic lithography)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:50

L22	873	21 and ((anti near reflective near coating) arc barc sion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:52
L23	236	22 and (polyimide (fluorinated adj polyimide) polysilsequioxane benzocyclobutene (parlene adj (n f)) (amorphous adj polytetrafluorothylene))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:52
L24	118	23 and (substrate with conductive)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:54
L25	174	23 and (substrate with (conductive metal))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:53